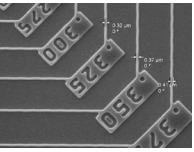
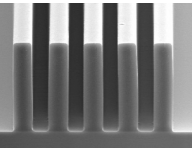
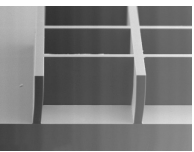



# SU-8 Technology

## Permanent Negative Epoxy Photoresists

Diverse Resist Options for Unique Needs

Product Line	Features	UV Sensitivity	Film Thickness (optimum)	Resolution
<b>SU-8 TF 6000</b>				
	<ul style="list-style-type: none"> <li>High resolution thin film processing</li> <li>Highly uniform thin films</li> <li>Improved substrate adhesion</li> </ul>	g-, h-, i-line	0.5–10 μm	High Resolution
<b>SU-8 3000</b>				
	<ul style="list-style-type: none"> <li>Improved substrate adhesion</li> <li>Reduced coating stress</li> </ul>	i-line	10–70 μm	>5:1 Aspect Ratio
<b>SU-8 2000</b>				
	<ul style="list-style-type: none"> <li>Improved substrate wetting</li> <li>Faster drying</li> <li>Higher process throughput</li> </ul>	i-line	10–100 μm	>10:1 Aspect Ratio
<b>SU-8</b>				
	<ul style="list-style-type: none"> <li>Wide range of viscosities</li> <li>High aspect ratio patterning</li> <li>Photo-definable ultra-thick structures</li> </ul>	i-line	10–200 μm	>10:1 Aspect Ratio

### APPLICATIONS

- MEMS
- Microfluidics
- Optoelectronics
- Displays